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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/996,864	11/19/2001	Cheng-Ku Chen	67,200-600	4851
75	90 11/22/2004		EXAMINER	
TUNG & ASSOCIATES			PHAM, LONG	
Suite 120 838 W. Long La	ake Road		ART UNIT PAPER NUMBER	
Bloomfield Hill			2814	
			DATE MAILED: 11/22/2004	4

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)					
	09/996,864	CHEN ET AL.					
Office Action Summary	Examiner	Art Unit					
	Long Pham	2814					
The MAILING DATE of this communication a Period for Reply	ppears on the cover sheet v	vith the correspondence ac	ddress				
A SHORTENED STATUTORY PERIOD FOR REF THE MAILING DATE OF THIS COMMUNICATION - Extensions of time may be available under the provisions of 37 CFR after SIX (6) MONTHS from the mailing date of this communication If the period for reply specified above is less than thirty (30) days, a r - If NO period for reply is specified above, the maximum statutory perions - Failure to reply within the set or extended period for reply will, by state that the period for reply will, by state that the material patent term adjustment. See 37 CFR 1.704(b).	N. 1.136(a). In no event, however, may a eply within the statutory minimum of the dwill apply and will expire SIX (6) MC tute, cause the application to become A	reply be timely filed rty (30) days will be considered time NTHS from the mailing date of this of the constant of the cons					
Status							
1) Responsive to communication(s) filed on 13	October 2004.						
2a)⊠ This action is FINAL . 2b)□ The	This action is FINAL . 2b) This action is non-final.						
•	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.						
Disposition of Claims							
4)⊠ Claim(s) <u>1,3-17,19 and 20</u> is/are pending in	☑ Claim(s) <u>1,3-17,19 and 20</u> is/are pending in the application.						
	4a) Of the above claim(s) is/are withdrawn from consideration.						
5) Claim(s) is/are allowed.							
6)⊠ Claim(s) <u>1,3-17, 19, and 20</u> is/are rejected.	Claim(s) <u>1,3-17, 19, and 20</u> is/are rejected.						
7) Claim(s) is/are objected to.							
8) Claim(s) are subject to restriction and	I/or election requirement.						
Application Papers							
9) The specification is objected to by the Exami	ner.						
10) ☐ The drawing(s) filed on is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.							
Applicant may not request that any objection to the	ne drawing(s) be held in abeya	nce. See 37 CFR 1.85(a).					
Replacement drawing sheet(s) including the corre	ection is required if the drawin	g(s) is objected to. See 37 C	FR 1.121(d).				
11)☐ The oath or declaration is objected to by the	Examiner. Note the attache	d Office Action or form P	TO-152.				
Priority under 35 U.S.C. § 119							
12) ☐ Acknowledgment is made of a claim for foreign	an priority under 35 U.S.C.	§ 119(a)-(d) or (f).					
a) ☐ All b) ☐ Some * c) ☐ None of:							
1. Certified copies of the priority documents have been received.							
2. Certified copies of the priority docume	ents have been received in .	Application No					
3. Copies of the certified copies of the pr	iority documents have bee	n received in this National	Stage				
application from the International Bure	, , , , , , , , , , , , , , , , , , , ,						
* See the attached detailed Office action for a li	st of the certified copies no	t received.					
			A* -				
Attachment(s)							
1) Notice of References Cited (PTO-892)		Summary (PTO-413)					
 Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/0 	🗂	(s)/Mail Date Informal Patent Application (PT	O-152)				
Paper No(s)/Mail Date	6) Other: _		,				

Art Unit: 2814

DETAILED ACTION

Rejections and/or objections as previously applied Claim Rejections - 35 USC § 102

- 1. The text of those sections of Title 35, U.S. Code not included in this action can be found in a prior Office action.
- 2. Claims 1, 3, and 4-7 are rejected under 35 U.S.C. 102(e) as being anticipated by Aminpur et al. (US '726).

With respect to claim 1, Aminpur et al. teaches a semiconductor device where during fabrication the semiconductor device comprises:

a primary layer 515 having a desired or specification or design dimension, fig. 5;

a lower layer 540 over the primary layer, fig. 5;

an upper layer 550 over the lower layer, the upper layer having a highetching selectivity as compared to the lower layer and the upper layer and lower layer have substantially identical width, fig.5 and col. 6, lines 53-55; and

an etching-stop layer 510 between the lower layer and primary layer, fig. 8 and associated text (that is during the formation of the gate 815).

Note that the process limitations in device claim 1 are given no weight in the patentability determination unless they produce some structural or material differences.

With respect to claim 3, Aminpur et al. further teach the primary layer comprises of a polysilicon layer. See col. 5, lines 10-15.

With respect to claims 4-7, Aminpur et al. further teach the lower and upper layers are made of Si₃N₄, SiON, or SiO₂. See col. 5, lines 40-50.

Art Unit: 2814

1. Claims 17, 19, and 20 are rejected under 35 U.S.C. 102(e) as being anticipated by Aminpur et al. (US '726).

With respect to claim 17, Aminpur et al. teaches a semiconductor device comprises:

a primary layer 515 having a desired or specification or design dimension, fig. 5;

a lower layer 540 over the primary layer, fig. 5;

an upper layer 550 over the lower layer, the upper layer having a highetching selectivity as compared to the lower layer and the upper layer and lower layer have substantially identical width, fig.5 and col. 6, lines 53-55; and

an etching-stop layer 510 between the lower layer and primary layer, fig. 8 and associated text (that is during the formation of the gate 815).

Note that the process limitations in device claim 17 are given no weight in the patentability determination unless they produce some structural or material differences.

With respect to claims 19-20, Aminpur et al. further teach the lower and upper layers are made of Si₃N₄, SiON, or SiO₂. See col. 5, lines 40-50.

Response to Arguments

2. Applicant's arguments filed 10/13/04 have been fully considered but they are not persuasive. See below.

Art Unit: 2814

In response to the applicant's arguments on page 6 of the applicant's response dated 10/13/04, it is submitted that the fig. 5, **NOT fig. 6 or the end product of Aminpur**, reads on the **end product** (lower and upper layers having identical width) of the **claimed** invention. Further, it is submitted that fig. 5 shows the lower and upper layers having identical width.

Conclusion

3. THIS ACTION IS MADE FINAL. Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Long Pham whose telephone number is 571-272-1714. The examiner can normally be reached on M-F, 7:30AM-3:00PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Wael Fahmy can be reached on 571-272-1705. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Art Unit: 2814

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Long Pham

Primary Examiner

Art Unit 2814